

SPUTTERING TARGET FOR MAGNETIC RECORDING MEDIUM, AND MAGNETIC THIN FILM

ABSTRACT

Provided is a sputtering target or a film which is characterized by containing 0.1 to 10 mol% of an oxide of one or more types selected from FeO, Fe₃O₄, K₂O, Na₂O, PbO, and ZnO, 5 to 70 mol% of Pt, and the the remainder being Fe. The present invention addresses the issue of providing a sputtering target capable of considerably reducing the particles caused by nonmagnetic materials and significantly improving the yield during deposition. It is thereby possible to deposit a quality magnetic recording layer and improve yield of a magnetic recording medium.

Fig. 1